

IN THE CLAIMS:

Please CANCEL claims 11-16 without prejudice to or disclaimer of the recited subject matter.

Please ADD new claims 17-25, as follows:

1-16.(Canceled)

17. (New) An exposure apparatus for exposing a substrate to light via a pattern of a reticle, said apparatus comprising:

a motor;

a first temperature adjustment system, having a flow path of pure water, configured to adjust temperature of said motor, and

a second temperature adjustment system, having a flow path of a coolant which is selected from the group consisting of a fluorine-based inert solution, a gas, and an antifreeze, configured to adjust temperature of an atmosphere including a path of the light.

18. (New) An apparatus according to claim 17, further comprising a stage configured to hold one of the reticle and the substrate, wherein said motor is configured to drive said stage.

19. (New) An apparatus according to claim 17, further comprising a projection optical system configured to project the pattern of the reticle onto the substrate, wherein said second

temperature adjustment system is configured to adjust temperature of said projection optical system.

20. (New) An apparatus according to claim 17, further comprising a conditioner, having a flow path of conditioning gas, configured to condition the atmosphere, wherein said second temperature adjustment system is configured to adjust temperature of the conditioning gas.

21. (New) An apparatus according to claim 18, wherein said first temperature adjustment system includes an impurity removing unit arranged upstream of said motor in the flow path of the pure water and configured to remove an impurity in the pure water.

22. (New) An apparatus according to claim 17, wherein the flow path of the pure water is a closed path.

23. (New) An apparatus according to claim 17, wherein said first and second temperature adjustment systems are configured to operate independently.

24. (New) An apparatus according to claim 17, further comprising:  
a projection optical system configured to project the pattern of the reticle onto the substrate, wherein said second temperature adjustment system is configured to adjust temperature of said projection optical system with a first coolant; and

a conditioner, having a flow path of conditioning gas, configured to condition the atmosphere, wherein said second temperature adjustment system is configured to adjust temperature of the conditioning gas with a second coolant different from the first coolant.

25. (New) A method of manufacturing a device, said method comprising steps of:  
exposing a substrate to light via a pattern of a reticle using an exposure apparatus as defined in claim 17;  
developing the exposed substrate; and  
processing the developed substrate to manufacture the device.